

Analysis methods of LED components

The optimal analytical methods are possible based on various LEDs characteristic even for a phosphor, a package, and a product from a light-emitting device.

Light emitting elements

Analysis subject	Endpoint	Methods of analysis
Element	Appearance form	<u>Optical microscope, SEM</u>
	Leak	<u>EL, SEM, TEM</u>
	Operating temperature	<u>Raman</u>
Surface, back electrode	Composition	<u>EPMA, AES, RBS</u>
	Impurities	<u>SIMS, TOF-SIMS, AES</u>
	Film thickness	<u>SEM, TEM</u>
	Oxide, surface contamination	<u>FT-IR, TOF-SIMS, AES, XPS</u>
	Stress	Strain gauge, XRD, Raman
	Roughness	<u>AFM, SEM</u>
	Adhesion	<u>Nanoindentation</u>
Cladding layer	Composition	<u>EPMA, AES, RBS, Raman, SIMS</u>
	Crystal defect	<u>PL, CL, TEM</u>
	Impurities	<u>SIMS, TOF-SIMS, ESR, Raman, CL</u>
	Carrier density	<u>SIMS, Raman, SCN</u>
	P/N structures	<u>SCM, SIMS</u>
Active layer	Structure, shape	<u>TEM</u>
	Film thickness	<u>TEM</u>
	Impurities	<u>SIMS, CL</u>
	Composition fluctuations	<u>STEM-EDX, CL</u>
Substrate, epitaxial films, buffer layer	Stress	<u>Raman, XRD, Strain gauge</u>
	A defect, crystalline	<u>PL, CL, Raman, XRD</u>
	Impurities	<u>SIMS, Raman</u>
	Grinding damage	<u>Raman, CL and AFM, X-ray topography</u>

LED package

Analysis subject	Endpoint	Methods of analysis
Mold resin	Composition	<u>FT-IR, solid state NMR, pyrolysis- GC/MS</u>
	Shape, a crack	<u>Optical microscope, SEM, X-ray analysis microscopes</u>
	Impurities	<u>FT-IR, NMR, ICP-MS</u>
	Degraded state	Solid state NMR, FT-IR, UV-VIS, ESR
	Hardness	<u>Nanoindentation</u>
	Heating resistance	DSC, TMA
	Adhesion	<u>Nanoindentation</u>
	Gas permeability	Steady state method differential pressure
	Water absorption rate	Vapor, gas adsorption measurements
Lead frame	Plating thickness	<u>SEM, TEM</u>
	Coefficient of thermal conductivity	Frash method
	Roughness, convex shape	<u>AFM, SEM</u>
	Surface contamination	<u>FT-IR, XPS and AES, TOF-SIMS</u>
	Discoloration, corrosion	<u>XPS, TOF-SIMS</u>
	Optical reflectance	UV-VIS
Electrical bonding	Loop shape (Wire)	<u>SEM, X-ray analysis microscopes</u>
	Delamination (wire) Solder, LCF	<u>SEM</u>
	Residual stress	<u>XRD, Raman</u>
Phosphor	Composition	<u>EPMA</u>
	Dimensional standard	<u>SEM</u>
	Degradation	Solid state NMR, FT-IR, UV-VIS, ESR, Raman, PL, CL

Notes: One element to measurement is possible for method of underline notation.

LEDs light etc.

Analysis subject	Endpoint	Methods of analysis
Chemical capacitors	Appearance form	<u>Optical microscope, SEM</u>
	Electrolyte deterioration	<u>FT-IR, HPLC</u>
	Corrosion of the electrodes	<u>X-ray CT, X-ray analysis microscopes, cross-section SEM</u>
Ceramic capacitors, Tantalum capacitors	Appearance form	<u>Optical microscope, SEM</u>
	Sintered body degradation	<u>SEM, CL</u>
	Internal disconnection	<u>X-rays analysis microscopes and fluoroscopically, opening observations</u>
	Impurities	<u>TOF-SIMS, EPMA</u>

Analysis subject	Endpoint	Method of analysis
Rectifier diode	Appearance form	<u>Optical microscope, SEM</u>
	Internal disconnection	<u>X-ray analysis microscopes and fluoroscopically, opening observations</u>
	Semiconductor device failure	<u>SEM, SCM</u>
Power transistor Other Electronic Components	Joint problems	<u>Optical microscope, SEM</u>
	Internal disconnection	<u>X-ray analysis microscopes, fluoroscopically, opening observations</u>
	Deformity	Strain gauge, XRD, Raman
	Insulation fracture	<u>An electrical properties tests, FT-IR</u>
	In addition, deterioration	<u>FT-IR, Solid state NMR, pyrolysis GC/MS</u>